



IPW

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q79878

Tomoya SASAKI

Appln. No.: 10/796,083

Group Art Unit: 1752

Confirmation No.: 2686

Examiner: Sin J. Lee

Filed: March 10, 2004

For: POSITIVE RESIST COMPOSITION AND METHOD OF FORMING A RESIST  
PATTERN USING THE SAME

**RESPONSE UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated November 16, 2004, please consider the  
remarks as submitted herewith on the accompanying pages.

3